

S/N TBD  
Docket: CS03 - 039  
Group art unit : \_\_\_ TBD

Date 11/21/2003

**To: Commissioner of Patents and Trademarks  
P.O. Box 1450 Alexandria, VA 22313-1450**

**Fr: William J. Stoffel      Reg. No. 39,390    Cust No. 30402  
PMB 455  
1735 Market St - Suite A  
Philadelphia, PA 19103**

Subject:

Serial No.      TDB Docket CS03 - 039 File Date: with application Inventor: Chen  <b>title: CMP Polishing Heads Retaining Ring Groove Design for Microscratch Reduction</b>  Group art unit: TBD
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**INFORMATION DISCLOSURE STATEMENT**

Enclosed is Form PTO A820 (also PTO-1449), Information Disclosure Citation and references.

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450, on Nov 24, 2003.

Signature/Date

William J. Stoffel  
William J. Stoffel Reg. No. 39,390  
Customer number 30402

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The following Patents and/or Publication are submitted to comply with the duty to disclose under CFR 1.97-1.99 and 37 CFR 1.56.

US 6,386,962B1(Gotkis et al.) that shows a wafer carrier with retainer ring for a chemical-mechanical polish (CMP) apparatus.

US 6,527,624 B1(Tollers et al.) shows a retaining ring.

US 6,110,025(Williams et al.) teaches a retainer ring with passages.

US 6,293,850 B1(Lin et al.) shows retaining ring with slurry passages at the bottom of the retainer ring.

US 6,224,472 B1(Lai et al.) teaches a retaining ring with channels.

Sincerely,

*with J. Stoffel*

William J. Stoffel  
Reg. No. 39,390  
Customer number 30,402

**INFORMATION DISCLOSURE CITATION**  
(Use several sheets if necessary)

Docket Number (Optional) cs03-039	Application Number
Applicant(s) chen et	
Filing Date	Group Art Unit

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		US 6,386,962B1		(Gotkis et al.)			
		US 6,527,624 B1		Tollers et al.)			
		US 6,110,025		Williams et al.)			
		US 6,293,850 B1		Lin et al.)			
		US 6,224,472 B1		Lai et al.			

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)


EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.